# On the implications of nitromethane - $NO_x$ chemistry interactions for combustion processes

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### **Supplementary Material**

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The detailed reaction mechanism provided as the supplement to this work includes both hydrocarbon and nitrogen chemistry. The mechanism also considers ammonia (NH<sub>3</sub>) as a fuel. In addition to fuel/NO<sub>x</sub> system mechanism can also be used to simulate the fuel blend with NH<sub>3</sub>.

#### 1. CH<sub>4</sub> oxidation doped with NO and NO<sub>2</sub>



**Figure S1:** Oxidation of CH<sub>4</sub>/O<sub>2</sub>/Ar doped with 500 ppm of NO in a JSR at  $\phi = 0.5$  and 1.07 bar. Symbols: experimental data from [1], Dashed lines: with CH<sub>3</sub>NO<sub>2</sub> chemistry, Solid lines: without CH<sub>3</sub>NO<sub>2</sub> chemistry.



**Figure S2:** Oxidation of CH<sub>4</sub>/O<sub>2</sub>/Ar doped with 500 ppm of NO in a JSR at  $\phi = 1.0$  and 1.07 bar. Symbols: experimental data from [1], Dashed lines: with CH<sub>3</sub>NO<sub>2</sub> chemistry, Solid lines: without CH<sub>3</sub>NO<sub>2</sub> chemistry.



**Figure S3:** Oxidation of CH<sub>4</sub>/O<sub>2</sub>/Ar doped with 500 ppm of NO in a JSR at  $\phi = 2.0$  and 1.07 bar. Symbols: experimental data from [1], Dashed lines: with CH<sub>3</sub>NO<sub>2</sub> chemistry, Solid lines: without CH<sub>3</sub>NO<sub>2</sub> chemistry.



**Figure S4:** Oxidation of CH<sub>4</sub>/O<sub>2</sub>/Ar doped with 400 ppm of NO<sub>2</sub> in a JSR at  $\phi = 0.5$  and 1.07 bar. Symbols: experimental data from [1], Dashed lines: with CH<sub>3</sub>NO<sub>2</sub> chemistry, Solid lines: without CH<sub>3</sub>NO<sub>2</sub> chemistry.



**Figure S5:** Oxidation of CH<sub>4</sub>/O<sub>2</sub>/Ar doped with 400 ppm of NO<sub>2</sub> in a JSR at  $\phi = 1.0$  and 1.07 bar. Symbols: experimental data from [1], Dashed lines: with CH<sub>3</sub>NO<sub>2</sub> chemistry, Solid lines: without CH<sub>3</sub>NO<sub>2</sub> chemistry.



**Figure S6:** Oxidation of CH<sub>4</sub>/O<sub>2</sub>/Ar doped with 400 ppm of NO<sub>2</sub> in a JSR at  $\phi = 2.0$  and 1.07 bar. Symbols: experimental data from [1], Dashed lines: with CH<sub>3</sub>NO<sub>2</sub> chemistry, Solid lines: without CH<sub>3</sub>NO<sub>2</sub> chemistry.



## 2. n-Heptane oxidation doped with and without NO

Figure S7: Reaction path analysis for n-C7H16/O2/N2/NO (500 ppm) based on C-atom at 740 K, 10 atm,  $\phi = 1.0$  and  $\tau = 1.0$  s.



**Figure S8:** HONO, HO<sub>2</sub> and OH concentration profiles during Oxidation of  $n-C_7H_{16}/O_2/N_2$  in JSR doped with (50 and 500 ppm NO) and without NO at 10 atm,  $\phi = 1.0$ ,  $\tau = 1.0$  s. Solid lines: prediction without CH<sub>3</sub>NO<sub>2</sub> chemistry, dashed lines: prediction with CH<sub>3</sub>NO<sub>2</sub> chemistry. Left figure (50 ppm NO), right figure (500 ppm of NO)



**Figure S9:** Oxidation of n-C<sub>7</sub>H<sub>16</sub>/O<sub>2</sub>/N<sub>2</sub> in JSR doped with 50 ppm of NO at 10 atm,  $\tau = 1.0$  s and different  $\phi$ . Symbols: measurements from [2], Solid lines: prediction without CH<sub>3</sub>NO<sub>2</sub> chemistry, dashed lines: prediction with CH<sub>3</sub>NO<sub>2</sub> chemistry.



**Figure S10:** OH, HO<sub>2</sub> and CH<sub>3</sub>NO<sub>2</sub> mole fraction profile comparison of n-heptane oxidation and methane oxidation in JSR. Solid lines: initial condition are same as in Figure 1 and 5, dashed lines: for n-heptane oxidation in JSR at  $\phi = 0.5$  and doped with 200 ppm of NO to have one to one comparison with methane.



**Figure S11:** Reaction path analysis for CH<sub>4</sub> oxidation in JSR for the condition shown in Figure 1 (doped with NO) based on N-atom at 900 K.

#### References

- Y. Song, L. Marrodán, N. Vin, O. Herbinet, E. Assaf, C. Fittschen, A. Stagni, T. Faravelli,
  M.U. Alzueta, F. Battin-Leclerc, The sensitizing effects of NO 2 and NO on methane low
  temperature oxidation in a jet stirred reactor, Proc. Combust. Inst. 37 (2019) 667–675.
  doi:10.1016/j.proci.2018.06.115.
- [2] G. Moréac, Experimental study and modelling of chemical interactions between gases residual and fresh gas in the homogeneous spontaneous ignition gasoline engines, PhD Thesis, University of Orléans, 2003. https://tel.archives-ouvertes.fr/tel-02961685/.